

L Number	Hits	Search Text	DB	Time stamp
1	0	\$fluoroadamantyl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 10:03
2	1	\$fluoro\$adamantyl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 10:11
9	997	fluoro\$6yl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:04
8	22	((("2000684888") or ("2003017415") or ("2003013039") or ("6602646") or ("6596458") or ("2002150835") or ("2001044070") or ("6579659")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 11:17
10	766	430/907.ccls. 430/905.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:04
11	6	(430/907.ccls. 430/905.ccls.) and (fluoro\$6yl adj (methacrylate acrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:04
12	247	(\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
13	6995	cyclo\$5yl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
14	12	(fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
15	905	fluoroalkyl near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
16	7916	(((\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist) ) (cyclo\$5yl adj (methacrylate acrylate) ) ((fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate) ) ) (fluoroalkyl near (methacrylate acrylate) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
17	72	(((\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist) ) (cyclo\$5yl adj (methacrylate acrylate) ) ((fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate) ) ) (fluoroalkyl near (methacrylate acrylate) )) and (430/907.ccls. 430/905.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
18	66	(((\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist) ) (cyclo\$5yl adj (methacrylate acrylate) ) ((fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate) ) ) (fluoroalkyl near (methacrylate acrylate) )) and (430/907.ccls. 430/905.ccls.) not ((430/907.ccls. 430/905.ccls.) and (fluoro\$6yl adj (methacrylate acrylate)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:24

19	0	2-fluoroadamantyl adj acrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:24
20	2	2-fluoroadamantyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:25
21	6	\$7fluoroadamantyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:51
22	4	\$7fluoronorbornyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:52
23	4	\$10fluoronorbornyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:53
24	3	\$10fluoroisobornyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:54
25	2	\$10fluoroisobornyl not \$10fluoronorbornyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:54
97	0	au-13035-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 13:46
98	0	au-88013035-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 13:46
-	1	("20030008231").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 10:02
-	75	fluorin\$8 near alicyclic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 10:25
-	246	\$10octafluoropentyl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 10:27
-	247	(\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:11
-	1	\$10fluor\$10adamantyl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 11:15
-	4397	(fluorine fluoro fluorinated) near5 (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 16:21
-	546	((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 10:36
-	546	((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)) not (fluorin\$8 near alicyclic )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:06
-	419	adamantyl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 11:30

-	0	(fluorine fluoro fluorinated) near (adamantyl adj (methacrylate acrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 11:16
-	6990	cyclo\$5yl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
-	0	2002363222.URPN.	USPAT	2003/09/08 13:35
-	1	2001JP-0170197.prai.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:05
-	904	fluoroalkyl near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
-	868	(fluoroalkyl near (methacrylate acrylate)) not (((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)) not (fluorin\$8 near alicyclic )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:06
-	5854256	s ((fluoroalkyl near (methacrylate acrylate)) not (((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)) not (fluorin\$8 near alicyclic ))) and (430/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:07
-	58	((fluoroalkyl near (methacrylate acrylate)) not (((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)) not (fluorin\$8 near alicyclic ) and (430/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:08
-	12	fluorocycloalkyl near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:19
-	44	\$fluorocyclo\$6yl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 15:27
-	44	(\$fluorocyclo\$6yl adj (methacrylate acrylate)) not (fluorocycloalkyl near (methacrylate acrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 16:20
-	302	alicyclic near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 16:20
-	366	(bicyclic polycyclic alicyclic) near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 16:20
-	12	(fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
-	17	(\$10fluorine \$10fluoro \$10fluorinated nonafluoro) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 16:25

ENTER SCREEN EXPRESSION OR (END):end

=>

Uploading C:\Program Files\Stnexp\Queries\10084828.str

L1 STRUCTURE UPLOADED

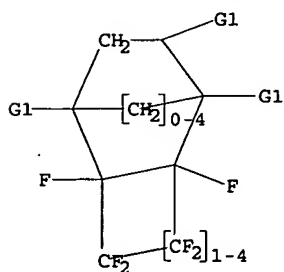
=> que L1

L2 QUE L1

=> d

L2 HAS NO ANSWERS

L1 STR



G1 H, F, Ak, CF3

*STN-search*  
*Do Not Remove*

Structure attributes must be viewed using STN Express query preparation.

L2 QUE ABB=ON PLU=ON L1

=> s l2 sss sam

SAMPLE SEARCH INITIATED 13:53:36 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 233 TO ITERATE

100.0% PROCESSED 233 ITERATIONS

SEARCH TIME: 00.00.01

0 ANSWERS

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*

BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 3745 TO 5575

PROJECTED ANSWERS: 0 TO 0

L3 0 SEA SSS SAM L1

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L4 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10084828-2.str

L5 STRUCTURE UPLOADED

=> que L5 AND L4

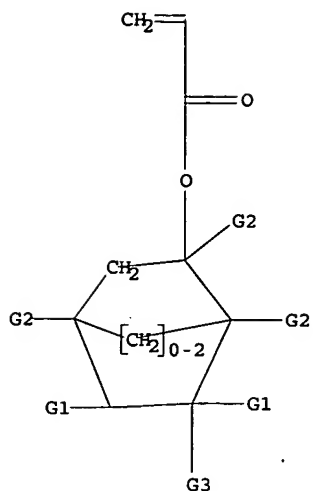
L6 QUE L5 AND L4

=> d

L6 HAS NO ANSWERS

L4 SCR 970 AND 2067

L5 STR



G1 H, F  
G2 H, F, CF3, Ak  
G3 F, CF2, CF3

Structure attributes must be viewed using STN Express query preparation.  
L6 QUE ABB=ON PLU=ON L5 AND L4

=> s l6 sss sam  
SAMPLE SEARCH INITIATED 13:54:27 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 28 TO ITERATE

100.0% PROCESSED 28 ITERATIONS 0 ANSWERS  
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 243 TO 877  
PROJECTED ANSWERS: 0 TO 0

L7 0 SEA SSS SAM L5 AND L4

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

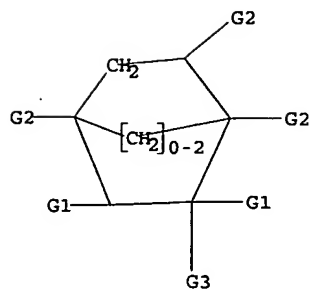
=>  
Uploading C:\Program Files\Stnexp\Queries\10084828-3.str

L8 STRUCTURE UPLOADED

=> que L8

L9 QUE L8

=> d  
L9 HAS NO ANSWERS  
L8 STR



G1 H,F  
G2 H,F,CF3,Ak  
G3 F,CF2,CF3

Structure attributes must be viewed using STN Express query preparation.  
L9 QUE ABB=ON PLU=ON L8

=> s l9 sss sam  
SAMPLE SEARCH INITIATED 13:55:02 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 14330 TO ITERATE

7.0% PROCESSED 1000 ITERATIONS 1 ANSWERS  
INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)  
SEARCH TIME: 00.00.01

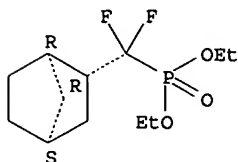
FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 279436 TO 293764  
PROJECTED ANSWERS: 59 TO 513

L10 1 SEA SSS SAM L8

=> d

L10 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS on STN  
RN 195258-93-6 REGISTRY  
CN Phosphonic acid, (bicyclo[2.2.1]hept-2-ylidifluoromethyl)-, diethyl ester,  
exo- (9CI) (CA INDEX NAME)  
FS STEREOSEARCH  
MF C12 H21 F2 O3 P  
SR CA  
LC STN Files: CA, CAPLUS

Relative stereochemistry.



\*\*PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT\*\*

1 REFERENCES IN FILE CA (1937 TO DATE)  
1 REFERENCES IN FILE CAPLUS (1937 TO DATE)

=> FIL HCAPLUS, CAPLUS, USPATFULL

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

3.28

3.49

FILE 'HCAPLUS' ENTERED AT 13:55:28 ON 08 SEP 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.  
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FILE 'CAPLUS' ENTERED AT 13:55:28 ON 08 SEP 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

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FILE 'USPATFULL' ENTERED AT 13:55:28 ON 08 SEP 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d his

(FILE 'HOME' ENTERED AT 13:52:58 ON 08 SEP 2003)

FILE 'REGISTRY' ENTERED AT 13:53:06 ON 08 SEP 2003

L1 STRUCTURE UPLOADED  
L2 QUE L1  
L3 0 S L2 SSS SAM  
L4 SCREEN 970 AND 2067  
L5 STRUCTURE UPLOADED  
L6 QUE L5 AND L4  
L7 0 S L6 SSS SAM  
L8 STRUCTURE UPLOADED  
L9 QUE L8  
L10 1 S L9 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 13:55:28 ON 08 SEP 2003

=> s 13 or 17 or 110

L11 2 L3 OR L7 OR L10

=> d l11 1-2 ibib hitstr

L11 ANSWER 1 OF 2 HCAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 1997:566255 HCAPLUS

DOCUMENT NUMBER: 127:234358

TITLE: Conjugate addition reactions of a  
(diethoxyphosphinoyl)difluoromethyl anion equivalent  
to acyclic and cyclic vinyl sulfones

AUTHOR(S): Blades, K.; Lapotre, D.; Percy, J. M.

CORPORATE SOURCE: Sch. Chemistry, Univ. Birmingham, Edgbaston,  
Birmingham, B15 2TT, UK

SOURCE: Tetrahedron Letters (1997), 38(33), 5895-5898

CODEN: TELEAY; ISSN: 0040-4039

PUBLISHER: Elsevier

DOCUMENT TYPE: Journal

LANGUAGE: English

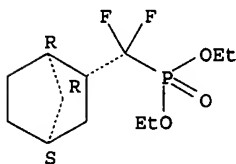
IT 195258-93-6P

RL: SPN (Synthetic preparation); PREP (Preparation)  
(prepn. of)

RN 195258-93-6 HCAPLUS

CN Phosphonic acid, (bicyclo[2.2.1]hept-2-yl)difluoromethyl-, diethyl ester,  
exo- (9CI) (CA INDEX NAME)

Relative stereochemistry.



L11 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 1997:566255 CAPLUS

DOCUMENT NUMBER: 127:234358

TITLE: Conjugate addition reactions of a  
(diethoxyphosphinoyl)difluoromethyl anion equivalent  
to acyclic and cyclic vinyl sulfones

AUTHOR(S): Blades, K.; Lapotre, D.; Percy, J. M.

CORPORATE SOURCE: Sch. Chemistry, Univ. Birmingham, Edgbaston,  
Birmingham, B15 2TT, UK

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CODEN: TELEAY; ISSN: 0040-4039

PUBLISHER: Elsevier

DOCUMENT TYPE: Journal

LANGUAGE: English

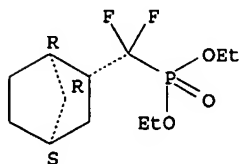
IT 195258-93-6P

RL: SPN (Synthetic preparation); PREP (Preparation)  
(prepn. of)

RN 195258-93-6 CAPLUS

CN Phosphonic acid, (bicyclo[2.2.1]hept-2-yl)difluoromethyl-, diethyl ester,  
exo- (9CI) (CA INDEX NAME)

Relative stereochemistry.





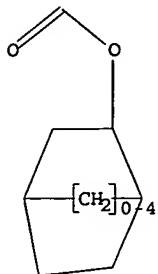
=> que L4

L5 QUE L4

=> d

L5 HAS NO ANSWERS

L4 STR



Structure attributes must be viewed using STN Express query preparation.  
L5 QUE ABB=ON PLU=ON L4

=> s 15 sss sam

SAMPLE SEARCH INITIATED 14:03:26 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 17471 TO ITERATE

5.7% PROCESSED 1000 ITERATIONS

27 ANSWERS

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 341515 TO 357325

PROJECTED ANSWERS: 8131 TO 10737

L6 27 SEA SSS SAM L4

=> d

L6 ANSWER 1 OF 27 REGISTRY COPYRIGHT 2003 ACS on STN

RN 565462-43-3 REGISTRY

CN Bicyclo[2.2.1]heptane-2-carboxylic acid, 2-(benzoylamino)-3-  
[(ethoxycarbonyl)oxy]-, ethyl ester, (1R,2R,3S,4S)-rel- (9CI) (CA INDEX  
NAME)

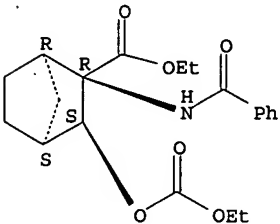
FS STEREOSEARCH

MF C20 H25 N O6

SR CA

LC STN Files: CA, CAPLUS

Relative stereochemistry.



\*\*PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT\*\*

1 REFERENCES IN FILE CA (1937 TO DATE)

1 REFERENCES IN FILE CAPLUS (1937 TO DATE)

=> FIL HCAPLUS, CAPLUS, USPATFULL

COST IN U.S. DOLLARS

SINCE FILE

ENTRY

TOTAL

SESSION

FULL ESTIMATED COST

4.96

5.17

FILE 'HCAPLUS' ENTERED AT 14:03:59 ON 08 SEP 2003  
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FILE 'USPATFULL' ENTERED AT 14:03:59 ON 08 SEP 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 16  
L7 139 L6  
  
=> s 17 and (photoresist or resist)  
L8 26 L7 AND (PHOTORESIST OR RESIST)  
  
=> s 18 and (fluor?)  
L9 7 L8 AND (FLUOR?)  
  
=> duplicates remove 19  
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'  
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n  
PROCESSING COMPLETED FOR L9  
L10 6 DUPLICATE REMOVE L9 (1 DUPLICATE REMOVED)  
  
=> d l10 1-6 ibib hitstr

L10 ANSWER 1 OF 6 USPATFULL on STN  
ACCESSION NUMBER: 2003:126971 USPATFULL  
TITLE: Polymer, resist composition and patterning  
process  
INVENTOR(S): Nishi, Tsunehiro, Niigata-ken, JAPAN  
Hasegawa, Koji, Niigata-ken, JAPAN  
Kinsho, Takeshi, Niigata-ken, JAPAN

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003087183	A1	20030508
APPLICATION INFO.:	US 2002-230341	A1	20020829 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-262833	20010831
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	BIRCH STEWART KOLASCH & BIRCH, PO BOX 747, FALLS CHURCH, VA, 22040-0747	
NUMBER OF CLAIMS:	4	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1550	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		
IT	521950-67-4P	

(polymer and resist compn. for deep-UV and electron beam patterning  
process)

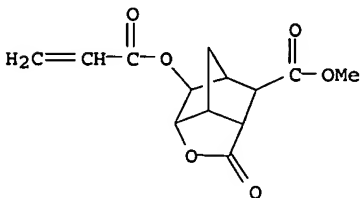
RN 521950-67-4 USPATFULL

CN 3,5-Methano-2H-cyclopenta[b]furan-7-carboxylic acid, hexahydro-2-oxo-6-[(1-oxo-2-propenyl)oxy]-, methyl ester, polymer with 2,5-furandione, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl 2-propenoate and spiro[bicyclo[2.2.1]hept-5-ene-2,3' (2'H)-furan]-5' (4'H)-one (9CI) (CA INDEX NAME)

CM 1

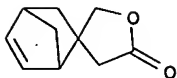
CRN 449759-66-4

CMF C13 H14 O6



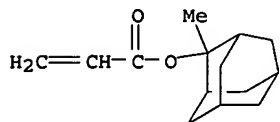
CM 2

CRN 282542-79-4  
CMF C10 H12 O2



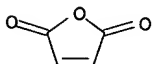
CM 3

CRN 249562-06-9  
CMF C14 H20 O2



CM 4

CRN 108-31-6  
CMF C4 H2 O3



L10 ANSWER 2 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2003:10538 USPATFULL

TITLE: Novel (meth) acrylates having lactone structure, polymers, photoresist compositions and patterning process

INVENTOR(S): Kinsho, Takeshi, Niigata-ken, JAPAN  
Hasegawa, Koji, Niigata-ken, JAPAN

PATENT ASSIGNEE(S): Watanabe, Takeru, Niigata-ken, JAPAN  
Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003008232	A1	20030109
APPLICATION INFO.:	US 2002-167444	A1	20020613 (10)

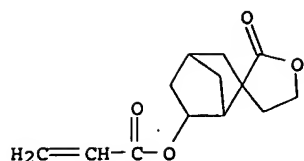
	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-179614	20010614
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201	
NUMBER OF CLAIMS:	8	
EXEMPLARY CLAIM:	1	
LINE COUNT:	729	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
IT 479072-45-2P

(lactone-contg. acrylate-based excimer laser-sensitive chem. amplified pos. photoresists with good transparency)

RN 479072-45-2 USPATFULL

CN 2-Propenoic acid, dihydro-2'-oxospiro[bicyclo[2.2.1]heptane-2,3'-(2'H)-furan]-6-yl ester (9CI) (CA INDEX NAME)



L10 ANSWER 3 OF 6 HCAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1  
 ACCESSION NUMBER: 2002:868986 HCAPLUS  
 DOCUMENT NUMBER: 137:370796  
 TITLE: Radiation-sensitive polysiloxane resin composition  
 INVENTOR(S): Iwasawa, Haruo; Hayashi, Akihiro; Shimokawa, Tsutomu;  
 Yamamoto, Masafumi  
 PATENT ASSIGNEE(S): JSR Co., Ltd., Japan  
 SOURCE: PCT Int. Appl., 155 pp.  
 CODEN: PIXXD2  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002090423	A1	20021114	WO 2002-JP4333	20020430
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
JP 2003020335	A2	20030124	JP 2002-48643	20020225
PRIORITY APPLN. INFO.:			JP 2001-133795	A 20010501
			JP 2002-48643	A 20020225

OTHER SOURCE(S): MARPAT 137:370796

IT 474559-57-4P

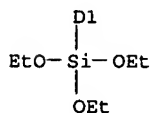
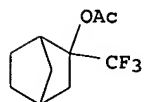
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP  
 (Properties); PREP (Preparation); USES (Uses)  
 (radiation-sensitive polysiloxane resin compn.)

RN 474559-57-4 HCAPLUS

CN Bicyclo[2.2.1]heptane-2-carboxylic acid, 5(or 6)-(triethoxysilyl)-2-  
 (trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with 5(or  
 6)-(triethoxysilyl)-.alpha.,.alpha.-bis(trifluoromethyl)bicyclo[2.2.1]hept  
 ane-2-ethanol and 5(or 6)-(triethoxysilyl)-2-(trifluoromethyl)bicyclo[2.2.  
 1]hept-2-yl acetate (9CI) (CA INDEX NAME)

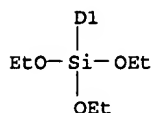
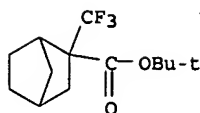
CM 1

CRN 474559-08-5  
 CMF C16 H27 F3 O5 Si  
 CCI IDS



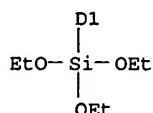
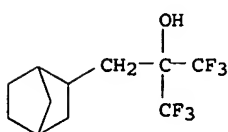
CM 2

CRN 474559-06-3  
 CMF C19 H33 F3 O5 Si  
 CCI IDS



CM 3

CRN 365546-74-3  
CMF C17 H28 F6 O4 Si  
CCI IDS



REFERENCE COUNT: 25 THERE ARE 25 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 4 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2002:119480 USPATFULL

TITLE: Polymer, resist composition and patterning process

INVENTOR(S): Nishi, Tsunehiro, Nakakubiki-gun, JAPAN  
Nakashima, Mutsuo, Nakakubiki-gun, JAPAN  
Tachibana, Seiichiro, Nakakubiki-gun, JAPAN  
Kinsho, Takeshi, Nakakubiki-gun, JAPAN  
Hasegawa, Koji, Nakakubiki-gun, JAPAN  
Watanabe, Takeru, Nakakubiki-gun, JAPAN  
Hatakeyama, Jun, Nakakubiki-gun, JAPAN

PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002061463	A1	20020523
APPLICATION INFO.:	US 2001-951523	A1	20010914 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2000-279164	20000914
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201	
NUMBER OF CLAIMS:	7	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1766	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
IT 409093-65-8P

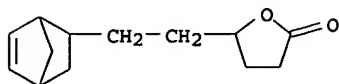
(polymers with cyclopentane rings in or adjacent to the chains for resists patternable by UV or electron beams)

RN 409093-65-8 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-ethylbicyclo[2.2.1]hept-2-yl ester, polymer with 5-(2-bicyclo[2.2.1]hept-5-en-2-ylethyl)dihydro-2(3H)-furanone and 2,5-furandione (9CI) (CA INDEX NAME)

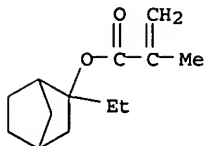
CM 1

CRN 370089-03-5  
CMF C13 H18 O2



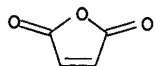
CM 2

CRN 330595-98-7  
CMF C13 H20 O2



CM 3

CRN 108-31-6  
CMF C4 H2 O3



L10 ANSWER 5 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2001:147641 USPATFULL

TITLE: Ester compounds, polymers, resist compositions and patterning process

INVENTOR(S): Kinsho, Takeshi, Nakakubiki-gun, Japan  
Nishi, Tsunehiro, Nakakubiki-gun, Japan  
Kurihara, Hideshi, Usui-gun, Japan  
Nakashima, Mutsuo, Nakakubiki-gun, Japan  
Hasegawa, Koji, Nakakubiki-gun, Japan  
Watanabe, Takeru, Nakakubiki-gun, Japan

PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, Japan (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6284429	B1	20010904
APPLICATION INFO.:	US 2000-512108		20000224 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-47406	19990225
	JP 1999-174945	19990622

DOCUMENT TYPE: Utility

FILE SEGMENT: GRANTED

PRIMARY EXAMINER: Ashton, Rosemary E.

LEGAL REPRESENTATIVE: Millen, White, Zelano & Branigan, P.C

NUMBER OF CLAIMS: 19

EXEMPLARY CLAIM: 1

LINE COUNT: 2016

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

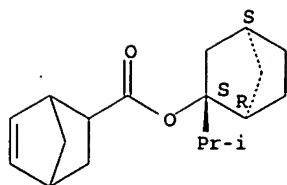
IT 290808-37-6P

(novel ester compds., polymers, resist compns. and patterning process)

RN 290808-37-6 USPATFULL

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, (1R,2S,4S)-2-(1-methylethyl)bicyclo[2.2.1]hept-2-yl ester, rel- (9CI) (CA INDEX NAME)

Relative stereochemistry.



L10 ANSWER 6 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2001:142042 USPATFULL  
 TITLE: Lactone-containing compounds, polymers, resist compositions, and patterning method  
 INVENTOR(S): Hasegawa, Koji, Nakakubiki-gun, Japan  
 Nishi, Tsunehiro, Nakakubiki-gun, Japan  
 Kinsho, Takeshi, Nakakubiki-gun, Japan  
 Hatakeyama, Jun, Nakakubiki-gun, Japan  
 Watanabe, Osamu, Nakakubiki-gun, Japan  
 PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, Japan (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6280898	B1	20010828
APPLICATION INFO.:	US 1999-404763		19990924 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1998-270373	19980925
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Baxter, Janet	
ASSISTANT EXAMINER:	Ashton, Rosemary	
LEGAL REPRESENTATIVE:	Millen, White, Zelano & Branigan, P.C.	
NUMBER OF CLAIMS:	21	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1654	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 274248-37-2P

(synthesis of lactone-contg. polymers for resist compns. and method of forming resist pattern using the compn.)

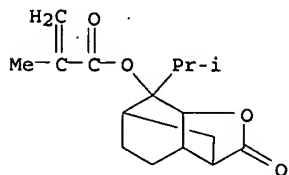
RN 274248-37-2 USPATFULL

CN 2-Propenoic acid, 2-methyl-, octahydro-7-(1-methylethyl)-2-oxo-3,6-methanobenzofuran-7-yl ester, polymer with tetrahydro-2H-pyran-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 274248-01-0

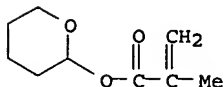
CMF C16 H22 O4



CM 2

CRN 52858-59-0

CMF C9 H14 O3



=> d his

(FILE 'HOME' ENTERED AT 10:15:29 ON 09 SEP 2003)

FILE 'REGISTRY' ENTERED AT 10:15:44 ON 09 SEP 2003

L1 SCREEN 963 AND 970 AND 1006 AND 2067  
L2 STRUCTURE UPLOADED  
L3 QUE L2 AND L1  
L4 15 S L3 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 10:17:00 ON 09 SEP 2003

L5 69 S L4  
L6 9 S L5 AND (FLUORINE OR FLUORINATED OR FLUORO)  
L7 8 DUPLICATE REMOVE L6 (1 DUPLICATE REMOVED)

=> d l7 1-8 ibib

L7 ANSWER 1 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:106118 USPATFULL  
TITLE: Positive-working resist composition  
INVENTOR(S): Sato, Kenichiro, Shizuoka, JAPAN  
Kodama, Kunihiro, Shizuoka, JAPAN  
Aoai, Toshiaki, Shizuoka, JAPAN  
PATENT ASSIGNEE(S): FUJII PHOTO FILM CO., LTD. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003073029	A1	20030417
APPLICATION INFO.:	US 2001-22363	A1	20011220 (10)
RELATED APPLN. INFO.:	Division of Ser. No. US 2000-684888, filed on 6 Oct 2000, PENDING		

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-285761	19991006
	JP 2000-80519	20000322
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	SUGHRUE MION, PLLC, 2100 Pennsylvania Avenue, NW, Washington, DC, 20037-3213	
NUMBER OF CLAIMS:	10	
EXEMPLARY CLAIM:	1	
LINE COUNT:	2718	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L7 ANSWER 2 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:23576 USPATFULL  
TITLE: Positive photosensitive composition  
INVENTOR(S): Kodama, Kunihiro, Shizuoka, JAPAN  
Sato, Kenichiro, Shizuoka, JAPAN  
PATENT ASSIGNEE(S): FUJII PHOTO FILM CO., LTD. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003017415	A1	20030123
APPLICATION INFO.:	US 2002-79414	A1	20020222 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-48602	20010223
	JP 2001-48783	20010223
	JP 2001-48784	20010223
	JP 2001-48880	20010223
	JP 2001-157366	20010525
	JP 2001-157367	20010525
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	SUGHRUE MION, PLLC, 2100 PENNSYLVANIA AVENUE, N.W., WASHINGTON, DC, 20037	
NUMBER OF CLAIMS:	19	
EXEMPLARY CLAIM:	1	
LINE COUNT:	3838	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L7 ANSWER 3 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:17287 USPATFULL  
TITLE: Resist composition and patterning process  
INVENTOR(S): Kobayashi, Tomohiro, Niigata-ken, JAPAN  
Nishi, Tsunehiro, Niigata-ken, JAPAN



Watanabe, Satoshi, Niigata-ken, JAPAN  
Kinsho, Takeshi, Niigata-ken, JAPAN  
Nagura, Shigehiro, Niigata-ken, JAPAN  
Ishihara, Toshinobu, Niigata-ken, JAPAN  
Shin-Etsu Chemical Co., Ltd., Tokyo, UNITED STATES,  
100-0004 (non-U.S. corporation)

PATENT ASSIGNEE(S):

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003013039	A1	20030116
APPLICATION INFO.:	US 2002-170345	A1	20020614 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-181079	20010615
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201	
NUMBER OF CLAIMS:	3	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1854	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L7 ANSWER 4 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:209927 USPATFULL  
TITLE: Positive-working resist composition  
INVENTOR(S): Sato, Kenichiro, Shizuoka, JAPAN  
Kodama, Kunihiro, Shizuoka, JAPAN  
Aoai, Toshiaki, Shizuoka, JAPAN  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, JAPAN (non-U.S.  
corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6602646	B1	20030805
APPLICATION INFO.:	US 2000-684888		20001006 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-285761	19991006
	JP 2000-80519	20000322
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Ashton, Rosemary	
LEGAL REPRESENTATIVE:	Sughrue Mion, PLLC	
NUMBER OF CLAIMS:	5	
EXEMPLARY CLAIM:	1	
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)	
LINE COUNT:	2562	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L7 ANSWER 5 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:197025 USPATFULL  
TITLE: Positive-working photoresist composition  
INVENTOR(S): Sato, Kenichiro, Shizuoka, JAPAN  
Kodama, Kunihiro, Shizuoka, JAPAN  
Aoai, Toshiaki, Shizuoka, JAPAN  
Kawabe, Yasumasa, Shizuoka, JAPAN  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, JAPAN (non-U.S.  
corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6596458	B1	20030722
APPLICATION INFO.:	US 2000-563436		20000503 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-127296	19990507
	JP 1999-186607	19990630
	JP 1999-193601	19990707
	JP 1999-193602	19990707
	JP 1999-193603	19990707
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Chu, John S.	
LEGAL REPRESENTATIVE:	Sughrue Mion, PLLC	
NUMBER OF CLAIMS:	8	
EXEMPLARY CLAIM:	1	

NUMBER OF DRAWINGS: 0 Drawing Figure(s); 0 Drawing Page(s)  
LINE COUNT: 1613  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 6 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2002:272716 USPATFULL  
TITLE: Polymer, resist composition and patterning process  
INVENTOR(S): Nishi, Tsunehiro, Nakakubiki-gun, JAPAN  
Nakashima, Mutsuo, Nakakubiki-gun, JAPAN  
Tachibana, Seiichiro, Nakakubiki-gun, JAPAN  
Funatsu, Kenji, Nakakubiki-gun, JAPAN  
PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S.  
corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002150835	A1	20021017
APPLICATION INFO.:	US 2002-73223	A1	20020213 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-37247	20010214
	JP 2001-37262	20010214
	JP 2001-37271	20010214
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201	
NUMBER OF CLAIMS:	4	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1682	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 7 OF 8 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1

ACCESSION NUMBER: 2001:143826 CAPLUS  
DOCUMENT NUMBER: 134:200525  
TITLE: Positive-working photoresist composition for far  
ultraviolet ray exposure  
INVENTOR(S): Aogo, Toshiaki; Sato, Kenichiro; Kodama, Kunihiro  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 55 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001056557	A2	20010227	JP 1999-234240	19990820
PRIORITY APPLN. INFO.:			JP 1999-234240	19990820

L7 ANSWER 8 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2001:212076 USPATFULL  
TITLE: Chemically amplified positive resist composition  
INVENTOR(S): Uetani, Yasunori, Osaka, Japan  
Yamada, Airi, Osaka, Japan  
Miya, Yoshiko, Muko-shi, Japan  
Takata, Yoshiyuki, Osaka, Japan

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2001044070	A1	20011122
	US 6579659	B2	20030617
APPLICATION INFO.:	US 2001-824227	A1	20010403 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2000-101868	20000404
	JP 2000-133328	20000502
	JP 2000-209505	20000711
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	BIRCH STEWART KOLASCH & BIRCH, PO BOX 747, FALLS CHURCH, VA, 22040-0747	
NUMBER OF CLAIMS:	5	
EXEMPLARY CLAIM:	1	
LINE COUNT:	894	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.